

**Amendments to the Claims:**

Claims 1- 6 (Canceled).

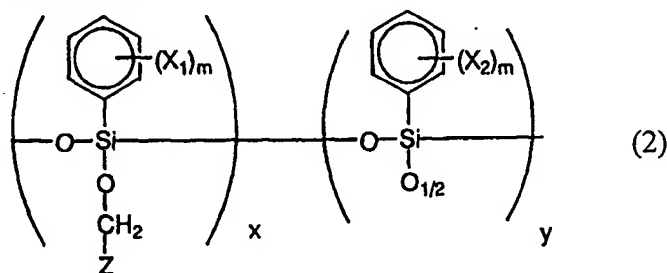
7. (Currently amended) A method of forming a polymer optical waveguide pattern, comprising the steps of:

forming a core layer of a photosensitive composition by a spin-coating method with a thickness which satisfies a single-mode condition of a resulting optical waveguide that comprises the core layer;

~~applying and drying~~ [[a]] the photosensitive composition for optical waveguides;  
irradiating said resultant photosensitive composition thin film for optical waveguides with light through a mask; and

directly forming a core-ridge pattern by wet etching said photosensitive composition thin film;

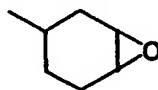
wherein the photosensitive composition for optical waveguides comprises an organic oligomer and a polymerization initiator, said organic oligomer being a silicone oligomer represented by the following formula (2):



wherein  $X_1$  and  $X_2$  may be the same as or different from each other, and denote hydrogen, deuterium, halogen, an alkyl group or an alkoxy group;  $m$  is an integer from 1 to 5;  $x$  and  $y$  designate the proportion of respective units, and  $y$  is smaller than  $x$  and may be 0; and  $Z$  denotes an epoxy group shown in the following formula (I) or (II):



(I)



(II)